

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant: *Gabric, et al.* Docket No.: INF 2006 VJ 33543 US

Serial No.: 10/586,788 Art Unit: 2893

Filed: September 2, 2008 Examiner: Nikolay K. Yushin

Conf. No.: 1598

For: Plasma Excited Chemical Vapor Deposition Method  
Silicon/Oxygen/Nitrogen-Containing-Material and Layered Assembly

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**AMENDMENT**

Dear Sir:

The following amendments and remarks are presented in response to the Examiner's Office Action mailed June 4, 2009. Please amend the above-referenced application as follows.